

高硅 Na-ZSM-5 分子筛表面 NO 的常温吸附-氧化机理

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摘要: 采用程序升温表面反应 (TPSR) 和原位漫反射红外光谱 (DRIFTS) 等手段研究了常温下 NO 和 O₂ 在高硅 Na-ZSM-5 分子筛上吸附-氧化反应机理. 结果表明, Na-ZSM-5 分子筛上 NO 的催化氧化过程中伴随着显著的 NO₂ 物理吸附, 表现为 NO 氧化和 NO₂ 吸附间的动态平衡. Na-ZSM-5 分子筛表面 NO_x 吸附物种的 TPSR 和原位 DRIFTS 表征表明, 化学吸附的 NO 和气相中的 O₂ 在 Na-ZSM-5 表面反应生成吸附态的 NO₃, 并继续与 NO 作用生成弱吸附的 NO₂ 和 N₂O₄, 它们吸附饱和后释放出来; 其中, 强吸附的 NO₃ 在 NO 氧化过程中起到了反应中间体的作用, 同时也促进了 NO 的吸附.

关键词: Na-ZSM-5 分子筛; 一氧化氮; 氧化; 氮氧化物; 吸附; 脱除

中图分类号: O643/X7

文献标识码: A

Adsorption-Oxidation Reaction Mechanism of NO on Na-ZSM-5 Molecular Sieves with a High Si/Al Ratio at Ambient Temperature

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Abstract: The oxidation reaction mechanism of NO by O₂ over Na-ZSM-5 molecular sieves with a high SiO₂/Al₂O₃ ratio was studied at ambient temperature by temperature-programmed surface reaction (TPSR) and in situ diffuse reflectance infrared Fourier transform spectroscopy (DRIFTS). The results show that the NO catalytic oxidation process is accompanied by a significant adsorption of NO₂ and it exhibits a dynamic equilibrium between NO₂ adsorption and the reaction of NO. TPSR and in situ DRIFTS characterization of the adsorbed NO_x species revealed that adsorbed NO₃ formed on the surface of the Na-ZSM-5 molecular sieve as a result of the reaction between adsorbed NO and gaseous O₂. The oxidation of NO₃ with NO produced weakly-adsorbing NO₂ and N₂O₄ which were released once the adsorption reached saturation. Therefore, the strongly-adsorbing NO₃ was an intermediate of the NO oxidation reaction and its presence promoted NO adsorption.

Key words: Na-ZSM-5 molecular sieve; nitric oxide; oxidation; nitrogen oxide; adsorption; removal

氮氧化物 (NO_x) 对生态环境和人类健康造成极大的危害, 脱除 NO_x 成为当前环境领域的重要研究课题之一. 选择性催化还原法 (SCR)、液体吸收法和吸附法是当前应用最广泛的技术, 这三种方法的处理效果都与 NO_x 中 NO₂ 的含量有关. Goo 等^[1] 发现在 V₂O₅-WO₃-MnO₂/TiO₂ 上的 NH₃-SCR 过程中, 提高 NO₂ 含量可大大降低反应温度, 最佳 NO₂:NO_x 比为

0.5; Koebel 等^[2] 指出, 当 NO₂:NO 为 1:1 时在 V₂O₅-WO₃/TiO₂ 上 SCR 活性最高. 而在碱液吸收法中要得到高的 NO_x 脱除率, 也必须提高 NO₂ 的含量. 当采用 NaOH 溶液吸收, 则需 NO₂:NO_x 比为 0.5~0.6^[3~5]; 若采用 (NH₄)₂SO₃-NaOH 等还原性碱液吸收, 所需要的 NO₂:NO_x 比更高^[6]. 在吸附法中由于 NO 难吸附, 只有将 NO 氧化成 NO₂ 才能获得较高的吸附量^[7]. 因

收稿日期: 2010-04-02.

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基金来源: 浙江省科技厅资助项目 (2007C23034).

本文的英文电子版由 Elsevier 出版社在 ScienceDirect 上出版 (<http://www.sciencedirect.com/science/journal/18722067>).

此, 如何将 NO_x 废气中占 90% 以上的 $\text{NO}^{[8]}$ 部分氧化成 NO_2 以提高 NO_x 脱除率, 是上述处理工艺共有的关键问题.

ZSM-5 分子筛及金属离子交换的 ZSM-5 应用于 NO_x 吸附和还原的研究较多^[9,10], 而有关以高硅 ZSM-5 为常温 NO 氧化催化剂鲜有报道. 针对活性炭和活性炭纤维在常温含水汽环境下氧化活性低^[11] 的缺点, 我们重点研究了高硅 ZSM-5 分子筛催化氧化 NO 性能, 发现该催化剂在高水汽含量气氛下具有远高于活性炭等材料的低温催化氧化活性^[12], 可望实现工业化应用. 因此, 本文进一步研究高硅 Na-ZSM-5 分子筛上 NO 和 O_2 的反应过程及表面吸附物种, 探讨 NO 常温吸附-氧化反应机理, 以期对后续的催化剂改进和反应动力学研究等提供理论指导.

1 实验部分

1.1 催化剂处理及活性评价

Na-ZSM-5 ($\text{SiO}_2/\text{Al}_2\text{O}_3 = 300$) 由上海卓悦化工有限公司提供. 分子筛原粉的处理及活性评价方法参见文献[12]. 反应条件: 催化剂装填量为 3.7 g, 反应气体积分数为 0.05% NO , 20.7% O_2 , N_2 平衡; 气体总流量 2 L/min, 反应温度 30 °C. 使用 Testo 350-XL 型烟气分析仪测定 NO 和 NO_2 进出口浓度.

1.2 催化剂表征

在进行程序升温表面反应 (TPSR) 时, 将 Na-ZSM-5 分子筛先于 500 °C, N_2 气中吹扫 2 h 后冷至 30 °C, 将 N_2 切换成 20.7% O_2 -79.3% N_2 , 0.05% NO -99.95% N_2 , 0.05% NO -20.7% O_2 -79.25% N_2 或 0.05% NO_2 -99.95% N_2 等不同的混合气进行吸附. 出口气体浓度用烟气分析仪检测. 吸附饱和后用 N_2 吹扫, 以除去表面上可逆吸附或弱吸附组分. 然后在 He 气 (20 ml/min) 中以 10 °C/min 从 30 °C 程序升温至 600 °C, 用 Omini Star 型质谱仪检测脱附物种.

在进行原位漫反射红外光谱 (DRIFTS) 测试时, 采用 VENTEX 70 型红外光谱仪进行 Na-ZSM-5 分子筛上 NO 和 O_2 反应, MCT 检测器, 分辨率为 4 cm^{-1} , 扫描 128 次. 把粉末状 ZSM-5 分子筛样品装入漫反射原位池中, 装满刮平, 在 400 °C 用 N_2 气 (100 ml/min) 吹扫 2 h 后将原位池冷却到设定温度, 测定不同温度下试样上未吸附反应物的 DRIFTS 谱, 将其作为相同温度下吸附反应物后的背景, 然后通入各种组成的

混合气进行吸附-反应, 并适时记录谱图.

2 结果与讨论

2.1 Na-ZSM-5 分子筛催化氧化 NO 瞬态反应研究

图 1 为 NO 和 O_2 流经高硅 Na-ZSM-5 催化剂床层后出口 NO 和 NO_2 浓度随时间的变化. 由图可见, 通入 NO 后很短的时间内进出口就出现 NO , 但浓度低于进口, 说明发生了 NO 的吸附, 而出口 NO_2 浓度极低. 随着时间的延长, 出口 NO 浓度不断增加, 到 60 min 后, 其浓度急剧减少, 而 NO_2 浓度快速增加, 至 65 min 后达到稳定状态, 进出口 NO_x 浓度平衡. 在相同条件下进行了空白实验, 发现在 5 min 内即可稳定, 出口 NO 浓度为 0.0497%, NO 的氧化可忽略, 而在装填 Na-ZSM-5 的反应器中有大量 NO_2 生成, 表明 Na-ZSM-5 确实起到了催化剂的作用.

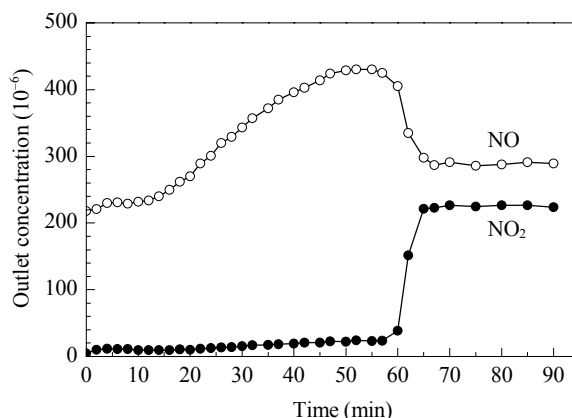


图 1 NO 在 Na-ZSM-5 上氧化反应瞬态变化曲线

Fig. 1. Transient NO oxidation profiles on Na-ZSM-5. Reaction conditions: NO 0.05%, O_2 20.7%, N_2 balance, 30 °C.

2.2 Na-ZSM-5 分子筛上 NO 氧化反应体系的 TPSR 研究

图 2 是 Na-ZSM-5 单独吸附 O_2 后的 TPSR 谱. 可以发现, 并未出现 O_2 脱附峰, 说明 O_2 在 Na-ZSM-5 上是不吸附的. 图 3 为 Na-ZSM-5 饱和吸附不同组成混合气后的 TPSR 谱. 其中图 3(a) 是分子筛单独吸附 NO 后的 TPSR 谱. 可以看出, 在 315 °C 附近出现宽的 NO 脱附峰, 说明存在 NO 的强化学吸附. 图 3(b) 是分子筛共吸附 NO 和 O_2 的 TPSR 谱. 与单独吸附 NO 相比, 分子筛上的 NO 脱附量明显增加, 与文献[6]结果一致, 且脱附温度范围更宽, 同时在 125 °C 出现 NO 脱附峰, 在 379 和 438 °C 处出现相互重叠的 NO 脱附峰, 而 315 °C 附近宽的 NO 脱附峰增强, 说明 O_2

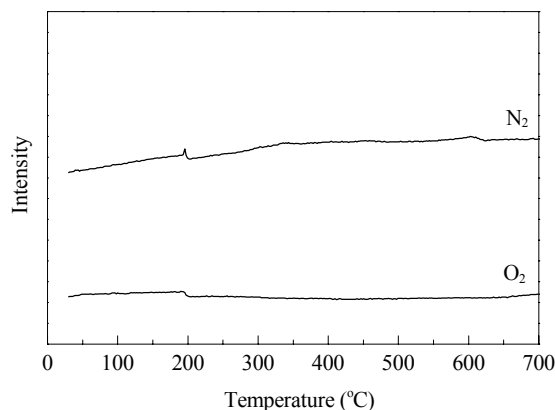


图2 Na-ZSM-5 单独吸附 O₂ 后的 TPRS 谱

Fig. 2. TPRS profiles after adsorption of 20.7%O₂-79.3%N₂ on Na-ZSM-5 catalyst.

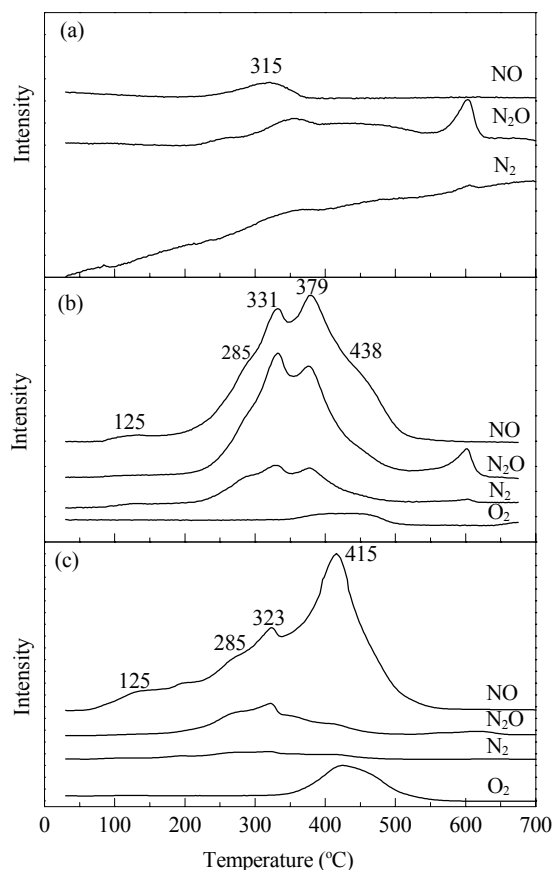


图3 Na-ZSM-5 上吸附不同 NO_x 气体组分后的 TPRS 谱

Fig. 3. TPRS profiles after adsorption of different gases on Na-ZSM-5 catalyst. (a) 0.05%NO-99.95%N₂; (b) 0.05%NO-20.7%O₂-79.25%N₂; (c) 0.05%NO₂-99.95%N₂.

的存在促进了 NO 的吸附. 刑娜等^[13]认为, NO 与 O₂ 作用形成 NO₂, 可与 NO 共吸附在分子筛表面形成 HNO₂ 物种, 程序升温时会脱附出 NO 和 NO₂, 但本文中 NO-O₂ 的 TPRS 谱中并未检测到 NO₂, 即使单独吸

附 NO₂(图 3(c)) 也仍未检测到 NO₂, 所以推测大部分 NO₂ 在分子筛表面为物理吸附, 或者在升温过程中发生了 NO₂ 分解. 同时, 图 3(b) 中 125 和 ~315°C 处宽的 NO 脱附峰与图 3(c) 相对应, 进一步说明图 3(b) 中这两处 NO 峰是 NO₂ 分解的产物. 图 3(b) 与 (c) 中在 400°C 附近都同时出现 NO 和 O₂ 峰, 可能来源于同一 NO_x 吸附物种, 即 NO 在分子筛上氧化为 NO₂ 中间体.

以上结果表明, NO 在 Na-ZSM-5 分子筛表面的氧化过程表现为类似 Eley-Rideal 反应机理, 即吸附的 NO 与气相中 O₂ 反应, 最终生成 NO₂.

图 3(a) 与 (b) 中出现的 N₂O 峰推断为高温下 NO 分解所致. 每个 N₂O 峰位置处都伴随着 N₂ 峰, 由于 N₂ 在催化剂表面不吸附, 排除了气相中 N₂ 的干扰, 因而该 N₂ 只能是 N₂O 进一步分解所得^[14].

2.3 Na-ZSM-5 分子筛上 NO 氧化反应体系的原位 DRIFTS 研究

图 4 为 30°C 下 0.1% NO 在 Na-ZSM-5 上吸附过程的原位 DRIFTS 谱. 由图可见, 随着时间的延长, 所有峰都在不断增强. 其中, 3 000~3 700 cm⁻¹ 处一般归属于 -OH 峰^[15], 2 min 时该峰处于 3 250 cm⁻¹, 到 10 min 时位移至 3 300 cm⁻¹ 处并增强, 表明 -OH 可能为 NO 吸附位. 3 300 和 2 900 cm⁻¹ 归属于分子筛桥式 -OH 位上吸附 NO 引起的红外吸收振动峰. 2 010

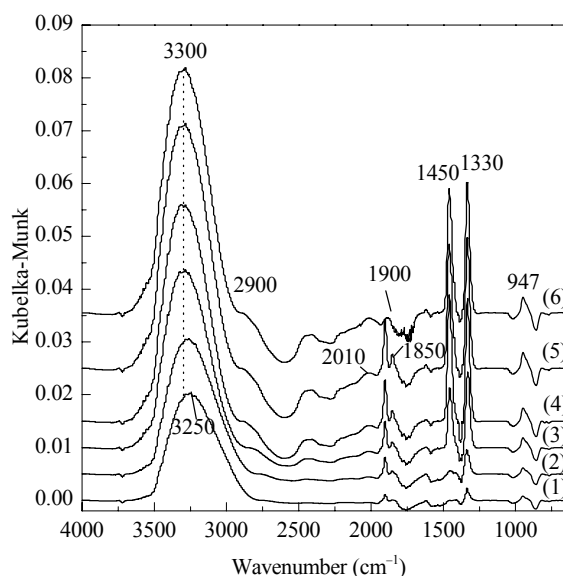


图4 Na-ZSM-5 分子筛上吸附 NO 的 DRIFTS 谱

Fig. 4. DRIFTS spectra of NO adsorbed on Na-ZSM-5 catalyst. (1) 2 min; (2) 5 min; (3) 10 min; (4) 15 min; (5) 20 min; (6) N₂ flushing after saturated adsorption.

cm^{-1} 处是吸附态 NO 的振动峰^[16]. 1 810~1 900 cm^{-1} 处一般归属于金属离子吸附 NO 引起的振动峰^[17,18], 因此, 1 850 和 1 900 cm^{-1} 归属于 Na-ZSM-5 上 Na^+ 吸附位上的 NO 振动峰. Perdana 等^[16]认为, 1 450 cm^{-1} 处也为 Na^+ 吸附 NO 的振动峰. 待 NO 吸附饱和后, 用 N_2 吹扫 10 min, 发现只有 1 900 和 1 850 cm^{-1} 处的峰变弱或消失, 其它峰强度均不变, 说明 Na^+ 上吸附的 NO 同时存在强弱两种吸附形式, 而 -OH 位上 NO 为较强吸附态.

图 5(a) 为 Na-ZSM-5 分子筛共吸附 NO 和 O_2 饱和后的 DRIFTS 谱. 可以看出, 对应于图 4 中的 2 010, 1 900, 1 850, 1 450 和 1 330 cm^{-1} 处峰全部消失, 说明这些活性位上吸附的 NO 都参与了氧化反应. 同时在 1 200~1 741 cm^{-1} 处出现新峰, 其中, 1 600 cm^{-1} 处峰最强, 为气相或弱吸附 NO_2 ^[19]; 1 200 和 1 630 cm^{-1} 归属于 NO_2 的吸附振动峰^[14,19]; 1 680 cm^{-1} 归属于 HNO_2 ^[15,20]; 1 260 和 1 310 cm^{-1} 处峰分别归属于 NO ^[21] 和 NO_3 的振动峰^[22], 而 1 741 cm^{-1} 为 N_2O_4 ^[23]. 说明 NO 氧化生成 NO_2 的过程中, 同时形成了 N_2O_4 和 NO_3 等中间物种.

待吸附饱和后停止通入 NO 和 O_2 , 用 N_2 吹扫后样品的 DRIFTS 谱见图 5(b). 可以看出, 所有 NO_2 峰 (1 200, 1 600 和 1 630 cm^{-1}) 均消失, 1 741 cm^{-1} 处

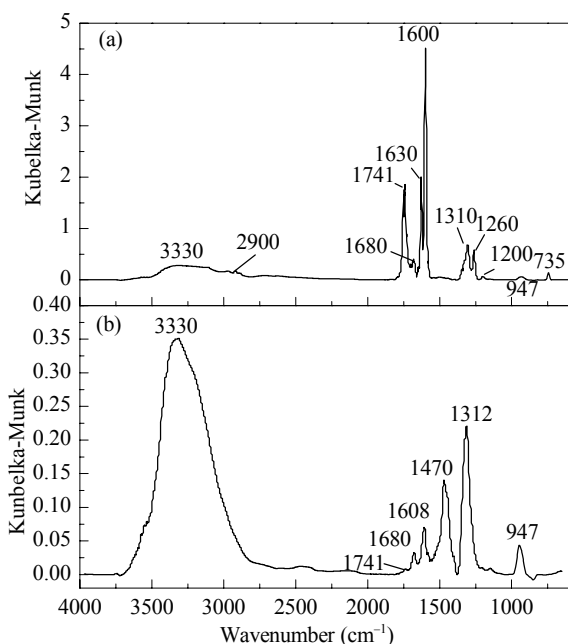


图 5 Na-ZSM-5 分子筛上共吸附 NO 和 O_2 的 DRIFTS 谱
Fig. 5. DRIFTS spectra of NO and O_2 co-adsorption on Na-ZSM-5 catalyst (a) before N_2 flushing; (b) after N_2 flushing.

N_2O_4 峰也大大减弱, 说明 NO_2 和 N_2O_4 在 Na-ZSM-5 上主要以弱吸附形式存在. 另外, 弱吸附态的 NO 峰 (1 260 cm^{-1}) 也消失, 而 NO_3 振动峰 (1 310 cm^{-1}) 仍存在. 1 608 和 1 470 cm^{-1} 处出现新的归属于 NO_3 的吸收峰^[15,16], 表明 NO 和 NO_2 脱附留下的空位可能为 NO_3 重新吸附而被占据.

利用 DRIFTS 谱研究了不同温度下 Na-ZSM-5 上 NO 和 O_2 的共吸附, 结果见图 6. 由图可见, 在 30 $^{\circ}\text{C}$ 下通入含 0.1% NO 和 20.7% O_2 的混合气, 待吸附饱和后用 N_2 吹扫除去分子筛表面气相分子, 可以观察到 3 300 (-OH), 1 741 (N_2O_4), 1 680 (HNO_2), 1 608, 1 470, 1 310 (NO_3) 以及 947 cm^{-1} (NO) 等红外振动峰; 当温度升至 90 $^{\circ}\text{C}$ 时, 1 741 和 1 680 cm^{-1} 处的红外峰消失, 而其余的峰都稍有减弱; 至 150 $^{\circ}\text{C}$ 时, 1 608 和 947 cm^{-1} 峰几乎消失, 只剩下 1 470 和 1 310 cm^{-1} 处的红外峰, 为强吸附态 NO_3 , 而 3 300 cm^{-1} 处的峰减弱并移至 3 370 cm^{-1} . 当温度升至 300 $^{\circ}\text{C}$ 时, 3 370 和 1 470 cm^{-1} 峰明显减弱, 而 1 310 cm^{-1} 处出现肩峰 (1 300 cm^{-1}) 并增强, 可能是 NO_3 开始分解生成新的物质. 当温度为 400 $^{\circ}\text{C}$ 时, 1 300 cm^{-1} 处峰继续增强, 并出现明显的 O_2 峰 (1 011 cm^{-1}). 结合 NO- O_2 -TPSR 谱中 ~400 $^{\circ}\text{C}$ 会有 NO 和 O_2 生成, 推断此温度下分解生成的 NO 和 O_2 来源于 NO_3 , 遵循反应式 $\text{NO}_3(\text{s}) \rightarrow$

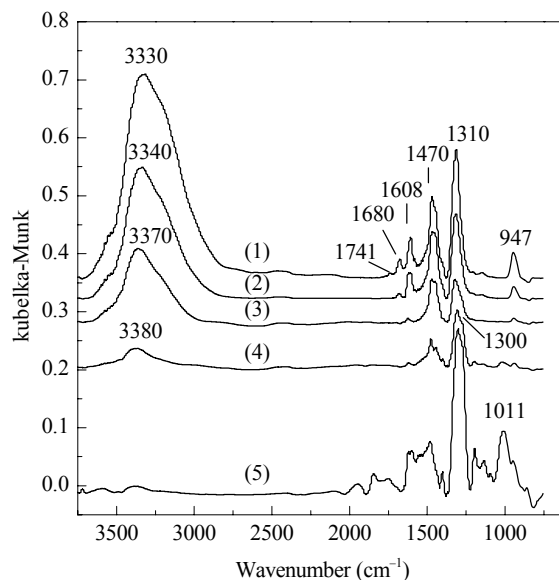


图 6 不同温度下 Na-ZSM-5 分子筛上吸附 NO 和 O_2 的 DRIFTS 谱

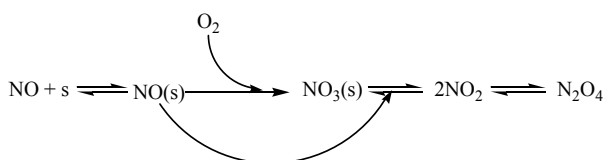
Fig. 6. DRIFTS spectra of NO and O_2 co-adsorption over Na-ZSM-5 at different temperatures. (1) 30 $^{\circ}\text{C}$; (2) 90 $^{\circ}\text{C}$; (3) 150 $^{\circ}\text{C}$; (4) 300 $^{\circ}\text{C}$; (5) 400 $^{\circ}\text{C}$.

$\text{NO}(\text{s}) + \text{O}_2$.

综合考虑 NO 和 O_2 共吸附后的 DRIFTS 和 TPSR 谱可知, NO 氧化生成的 NO_2 及 N_2O_4 在分子筛上大部分是以弱吸附态或气态存在, 经 N_2 吹扫即发生脱附; 而小部分可转化成强吸附态的 NO_3 , 在高温下分解成 NO 和 O_2 而脱附. 因此在分子筛共吸附 NO 和 O_2 的 TPSR 谱中检测不到 NO_2 .

2.4 NO 吸附-氧化过程机理分析

综上所述, 常温下 NO 和 O_2 在分子筛表面反应后形成 NO_2 , N_2O_4 , NO_3 和 NO 等中间物种. 根据这些中间物种的形成及吸附强度, 可以推测 NO 和 O_2 在高硅 Na-ZSM-5 分子筛上的反应机理为: NO 首先吸附在分子筛活性位上, 吸附态 NO 与气相中的 O_2 反应生成吸附态 NO_3 , 然后进一步与吸附态 NO 作用转化为 NO_2 和 N_2O_4 , 如图式 1 所示.



图式 1 高硅 Na-ZSM-5 分子筛上 NO 氧化反应机理

Scheme 1. Mechanism of NO oxidation over high silica Na-ZSM-5 molecular sieves.

在反应开始阶段, NO 的吸附及其与 O_2 的反应为主要过程, 生成强吸附态 NO_3 , 并继续与吸附的 NO 反应生成弱吸附态的 NO_2 和 N_2O_4 , 此时无 NO_2 释放, NO 出口浓度变化不大, 相当于图 1 中 0~15 min 这一时间段. 随着反应的进行, Na-ZSM-5 表面 NO_2 和 N_2O_4 的吸附量逐渐增加, 上述反应受到抑制, 此时 NO 出口浓度缓慢增加, 相当于图 1 中 15~60 min 时间段, 为第二过程. 随着 NO_2 吸附饱和而释放, 又进一步促进了 NO 与 NO_3 的反应, NO 出口浓度急剧下降, 上述两个过程同时进行, 相互作用, 最终达到吸附-氧化动态平衡. 此机理解释了 NO 和 O_2 氧化过程中的瞬态变化曲线, 以及 NO- O_2 -TPSR 和 NO_2 -TPSR 中没有检测到 NO_2 、分子筛表面吸附态 NO_3 在高温下分解形成 NO 和 O_2 等现象.

3 结论

常温下高硅 Na-ZSM-5 分子筛具有催化氧化 NO 的性能, 主要吸附活性位是 $-\text{OH}$ 和 Na^+ , 在催化氧

化 NO 的过程中, 大部分 NO_2 在分子筛上是以物理吸附的形式存在. NO 和 O_2 的反应机理为: NO 首先吸附在分子筛活性位上, 化学吸附的 NO 与气相 O_2 反应生成吸附的 NO_3 , 并继续与吸附的 NO 作用转化成 NO_2 和 N_2O_4 , 当其达到饱和吸附后释放出来, 从而达到吸附-氧化的动态平衡; 强吸附的 NO_3 在 NO 氧化过程中起到中间体的作用, 同时也促进了 NO 的吸附.

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英 译 文 English Text

The abatement of nitric oxides (NO_x) is an important challenge because NO_x compounds are a source of severe eco-environmental problems and are harmful to human health. Selective catalytic reduction (SCR), absorption, and adsorption are widely applied in the NO_x emission control area. To increase the removal efficiency of NO_x , it is beneficial to maintain a high ratio of NO_2/NO_x in the feed. Goo et al. [1] concluded that the presence of NO_2 enhances the SCR activity at lower temperature and the optimum ratio of NO_2/NO_x was found to be 0.5 for the $\text{V}_2\text{O}_5\text{-WO}_3\text{-MnO}_2/\text{TiO}_2$ catalyst in the $\text{NH}_3\text{-SCR}$ process. Koebel et al. [2] obtained similar results, that is, equimolar amounts of NO and NO_2 led to the highest NO_x conversion over the $\text{V}_2\text{O}_5\text{-WO}_3/\text{TiO}_2$ catalyst. For absorption by alkaline aqueous solutions, a high NO_2/NO_x ratio is required to obtain high NO_x removal efficiency. Generally, a 0.5–0.6 fraction of NO_2 in NO_x is required during the NaOH solution absorption process since NO_x compounds are removed primarily by the formation of N_2O_3 from the reaction of NO with NO_2 [3–5]. Furthermore, the required fraction would be much higher if a $(\text{NH}_4)_2\text{SO}_3\text{-NaOH}$ solution was used for absorption because the reduction of $(\text{NH}_4)_2\text{SO}_3$ with NO_2 is much stronger than that with NO [6]. Because NO has difficulty adsorbing onto the surface of adsorbents, NO has to be oxidized to NO_2 first and then a high adsorption volume can be obtained [7]. Unfortunately, the NO_x in power station or industrial plant exhaust gases typically consist of more than 90% NO [8], which means that the fractional oxidation of NO to NO_2 is a key step in all NO_x abatement processes.

Many studies have been done on ZSM-5 molecular sieves and ion-exchanged ZSM-5, which is used for NO_x adsorption and reduction [9,10]. Only a few of these studies have focused on NO oxidation, especially at ambient temperature. Instead, activated carbon (AC) and active carbon fiber (ACF) have widely been reported to be used as catalysts for NO oxidation. AC and ACF, however, have a high adsorption volume for vapor, which is preferred over NO_x adsorption and this leads to low catalytic activity for NO oxidation and limits their application in industry [11]. Accordingly, a highly hydrophobic surface can be obtained on molecular sieves with a high Si/Al ratio and our early research empha-

sized the high silica content ZSM-5 molecular sieve for NO oxidation. The results confirmed that far higher catalytic activity can be obtained for ZSM-5 than for AC or ACF under high vapor conditions [12], which means that the ZSM-5 catalyst has potential industrial application. Based on these results, for this paper we focused on the reaction pathway between NO and O_2 , and also on the species adsorbed on the surface of the high silica content Na-ZSM-5. Furthermore, we discuss the reaction mechanism. We hope that this work provides a theoretical direction for the improvement of catalytic activity and for the study of the reaction kinetics of ZSM-5.

1 Experimental

1.1 Catalyst treatment and the adsorption-reaction test

Na-ZSM-5 ($\text{SiO}_2/\text{Al}_2\text{O}_3$ molar ratio of 300) was provided by Shanghai Zhuoyue Chemicals Co., Ltd. The methods used for catalyst treatment and the reaction test have been reported in Ref. [12]. The main operation conditions in the adsorption-reaction tests were as follows: catalyst loading 3.7 g; molar fraction of NO and O_2 of 0.05% and 20.7%, respectively, in the inlet NO_x mixed gas with N_2 as the balance; total flow rate 2 L/min; reaction temperature 30 °C. The concentrations of NO and NO_2 in the gas stream were measured using a Testo 350-XL flue gas analyzer.

1.2 Catalyst characterization

Temperature-programmed surface reaction (TPSR): the Na-ZSM-5 molecular sieves were flushed by a N_2 gas stream at 500 °C for 2 h and then cooled down to a specific temperature that varied from 30 °C to 400 °C. This was followed by the adsorption of a mixed gas with different components including 20.7% $\text{O}_2\text{-79.3}\%\text{N}_2$, 0.05% $\text{NO-99.95}\%\text{N}_2$, 0.05% $\text{NO-20.7}\%\text{O}_2\text{-79.25}\%\text{N}_2$, 0.05% $\text{NO}_2\text{-99.95}\%\text{N}_2$ etc. The outlet concentrations of NO and NO_2 were measured using a Testo 350-XL flue gas analyzer. After saturated adsorption was obtained, the surface of the catalyst was flushed with a N_2 gas stream again to remove the weakly adsorbed surface species. Finally, temperature programmed desorption was done at a heating rate of 10 °C/min from 30 °C to 600 °C and the desorbed species were detected using the Omini-Star mass spectrometer.

The reaction of NO and O_2 on the surface of Na-ZSM-5 was further investigated using a VENTEX 70 infrared spectrometer equipped with a MCT detector at a resolution of 4 cm^{-1} (128 scans). The Na-ZSM-5 powders were first placed in a diffuse in situ cell, flushed with a N_2 gas stream at 400 °C for 2 h and then cooled to the specific reaction temperature. The diffuse IR spectra of the Na-ZSM-5 catalyst were first

measured at different temperatures as the corresponding reference, and then a mixed gas with different components was introduced into the in situ cell for adsorption and reaction. The diffuse reflectance infrared Fourier transform spectroscopy (DRIFTS) spectra were recorded at regular time intervals.

2 Results and discussion

2.1 Transient profiles of the NO catalytic oxidation on the Na-ZSM-5 molecular sieves

The trend of outlet NO and NO₂ concentrations with time is shown in Fig. 1. As soon as the NO_x mixed gas passed through the reactor, NO was detected in the outlet but the concentration of NO was less than that in the inlet and the NO₂ concentration was too low to be detected in the first period, which means that adsorption takes place on the surface of ZSM-5. With time, the outlet NO concentration increased slowly until it reached 60 min on stream upon which it decreased sharply. At the same time, the outlet concentration of NO₂ began to increase sharply. Finally, the adsorption-reaction process reached a steady state at around 65 min when the outlet concentration of NO_x was equal to that of the inlet. On the contrary, for the blank experiment where the reactor was used without ZSM-5 catalyst packing under the same operating conditions, a steady state was reached within 5 min and the outlet NO concentration was 0.0497% (equal to that of inlet). Therefore, the oxidation of NO can be neglected in the blank reactor. These experiments prove that the Na-ZSM-5 molecular sieve shows a catalytic effect toward NO oxidation by O₂ at ambient temperature.

2.2 TPSR measurements of NO oxidation over Na-ZSM-5

Figure 2 shows TPSR profiles of the O₂ and N₂ adsorbed on Na-ZSM-5. No oxygen was detected during the TPSR and this is possibly because of O₂ not adsorbing on Na-ZSM-5. Figure 3 shows TPSR profiles for the saturated adsorption of NO_x on Na-ZSM-5. A desorption peak is present at 315 °C in the TPSR profile of individually adsorbed NO on Na-ZSM-5 (Fig. 3(a)), which means that there exists NO adsorption strongly. Figure 3(b) shows the TPSR profile of NO/O₂ co-adsorption. Similar to the phenomena in Ref. [6], the amount of NO released during TPSR increased remarkably compared to that of single NO adsorption. The intensity of the peak at 315 °C increased and more NO desorption peaks appeared at 125, 379, and 438 °C. The latter two peaks overlap because of the wider temperature range. The presence of O₂ in the mixed NO_x gas promotes NO adsorption on Na-ZSM-5. Xing et al. [13] postulated that NO₂ from the

reaction of NO with O₂ could co-adsorb with NO on the surface of Na-ZSM-5 and form a HNO₂ specie, which would desorb from the surface of Na-ZSM-5 by the form of NO and NO₂ during the followed TPD program. In our study, NO₂ was not detected during the TPSR measurement of NO/O₂ co-adsorption and NO₂ single adsorption (Fig. 3(c)) so we conclude that NO₂ exists on the surface of Na-ZSM-5 through the physical adsorption. The possibility of NO₂ decomposition during TPSR should, however, not be ignored. Nevertheless, the desorption peaks at 125 and ~315 °C are present in Fig. 3(b) and in Fig. 3(c), which means that these desorbed species originate from the products of NO₂ decomposition. From Fig. 3(b) and 3(c), both the NO and O₂ desorption peaks exist simultaneously at 400 °C and they might originate from the same adsorbed species, i.e., the intermediate from the reaction of NO to NO₂ conversion on the surface of Na-ZSM-5.

From the TPSR measurements, the oxidation process of NO by O₂ on the surface of Na-ZSM-5 followed the Eley-Rideal reaction mechanism, that is, the adsorbed NO reacts with gaseous O₂ and forms NO₂.

In addition, the desorbed N₂O species at 315 and 379 °C probably originate from the decomposition of NO at high temperature. Also, the release of N₂ accompanied by N₂O comes from the further decomposition of N₂O [14] because N₂ does not adsorb on Na-ZSM-5 according to Fig. 2.

2.3 In situ DRIFTS characterization of NO oxidation on Na-ZSM-5

Figure 4 shows the in situ DRIFTS spectra of the adsorption process for 0.1% NO on Na-ZSM-5. With an increase in the adsorption time, the strength of all the adsorption peaks increased. The strongest peak changed from 3 250 to 3 300 cm⁻¹ and the intensity increased continuously, which indicates that the -OH group on the surface of Na-ZSM-5 might be an adsorption site for NO since the peaks at 3 000–3 700 cm⁻¹ are usually assigned to species adsorbed on -OH sites [15]. The peaks at 3 300 and 2 900 cm⁻¹ are assigned to the IR vibration of adsorbed NO on the bridge-linked -OH group of Na-ZSM-5. The peak at 2 010 cm⁻¹ is assigned to the vibration of adsorbed NO [16]. The adsorption peaks at 1 450, 1 850, and 1 900 cm⁻¹ are associated with the IR vibration of adsorbed NO on the Na⁺ site of the Na-ZSM-5 molecular sieve [16–18]. When Na-ZSM-5 is flushed for 10 min using a N₂ stream after the saturated adsorption of NO, we found that only the peaks at 1 900 and 1 850 cm⁻¹ weakened and even disappeared, as shown in Fig. 4(6), which indicates that two types of the adsorption sites exist simultaneously on the surface of Na-ZSM-5, i.e., one is a strong adsorption site and the other a weak one. The -OH group would be associated with the stronger one.

Figure 5(a) shows the DRIFTS spectra for saturated NO/O₂ co-adsorption on Na-ZSM-5. From the spectra, we found that the peaks at 2 010, 1 900, 1 850, 1 450, and 1 330 cm⁻¹ in Fig. 4 disappeared, which suggests that all the adsorbed NO on these sites took part in the oxidation reaction. At the same time, new peaks appeared between 1 200–1 741 cm⁻¹ including the strongest peak at 1 600 cm⁻¹, which is assigned to gaseous or weakly adsorbed NO₂ [19], the adsorption vibration of NO₂ at 1 200 and 1 630 cm⁻¹ [14,19], HNO₂ at 1 680 cm⁻¹ [15,20], the vibration of NO [21] and NO₃ [22] at 1 260 and 1 310 cm⁻¹, respectively as well as N₂O₄ at 1 741 cm⁻¹ [23]. From this data, N₂O₄ and NO₃ adsorbed species are obviously formed during the oxidation reaction of NO to NO₂.

After saturation of the NO/O₂ adsorption, Na-ZSM-5 was flushed with N₂ gas, and IR spectra were recorded at different times. Compared to the spectra in Fig. 5(a), all the NO₂ peaks at 1 200, 1 600, and 1 630 cm⁻¹ disappeared and the N₂O₄ peak at 1 741 cm⁻¹ weakened, as shown in Fig. 5(b), which means that the adsorption of NO₂ and N₂O₄ on the surface of Na-ZSM-5 is because of a weak physical adsorption. Although the weakly adsorbed NO peak at 1 260 cm⁻¹ also disappears, the NO₃ vibration peak at 1 310 cm⁻¹ still exists. Nevertheless, after flushing with a N₂ stream, the new IR peaks at 1 608 and 1 470 cm⁻¹ are assigned to the adsorbed NO₃ species [15,16]. This might originate from vacant sites that result from NO and NO₂ desorption. Therefore, the NO₃ species might originate from strong adsorption on Na-ZSM-5.

The effects of temperature on the co-adsorption of NO/O₂ on Na-ZSM-5 were further investigated using in situ DRIFTS. First, the mixed gas containing 0.1% NO and 20.7% O₂ was introduced into the diffuse in situ cell. When saturated adsorption was reached, Na-ZSM-5 was flushed using a N₂ gas stream and gradually heated. The IR spectra are shown in Fig. 6. When the temperature was kept at 30 °C, peaks were present at 3 300 (NO), 1 741 (N₂O₄), 1 680, 1 470, 1 310 (NO₃), and 947 cm⁻¹ (NO). When the temperature was increased to 150 °C, the peaks at 1 741 and 1 680 (90 °C), 1 608 and 947 cm⁻¹ (150 °C) disappeared in this sequence and only the peaks at 1 470 and 1 310 cm⁻¹ that are assigned to the strongly adsorbed NO₃ species are left. The peak at 3 300 cm⁻¹ decreased in intensity and blue-shifted to 3 370 cm⁻¹. When the temperature was increased to 300 °C, the peaks at 3 370 and 1 470 cm⁻¹ weakened significantly. Conversely, the peak at 1 310 cm⁻¹ accompanied by the shoulder peak at 1 300 cm⁻¹ strengthened, which means that a new specie was formed from the reaction of NO₃. When the temperature increased to 400 °C, the peak at 1 300 cm⁻¹ continued to strengthen and an intensive peak was present at 1 101 cm⁻¹ and is assigned to O₂. Based on these results, it is inferred that the newly formed NO and O₂

originated from the decomposition of the adsorbed NO₃ intermediate according to the following equation: NO₃(s) → NO(s) + O₂.

Furthermore, according to TPSR and DRIFTS characterization of the NO/O₂ co-adsorption, most of the NO₂ and N₂O₄ formed by the oxidation of NO were weakly physically adsorbed on the Na-ZSM-5 molecular sieve or existed in the gas phase and, therefore, were easily desorbed or flushed out by N₂. The others were converted into strongly adsorbed NO₃ species, which decomposed further into NO and O₂ and then desorbed from the surface of Na-ZSM-5 at high temperature. Therefore, NO₂ was hardly detected in the TPSR spectra for NO/O₂ co-adsorption.

2.4 Analysis of the adsorption-oxidation reaction mechanism of NO by O₂

From the study of DRIFTS and TPSR, some intermediates such as NO₂, N₂O₄, and NO₃ obviously formed during the surface reaction of NO with O₂ on Na-ZSM-5 at ambient temperature. Based on these results, the adsorption and reaction pathway of NO with O₂ on the surface of Na-ZSM-5 was further analyzed. First, gaseous NO is adsorbed on the surface of Na-ZSM-5 chemically and then the adsorbed NO species reacts with gaseous O₂ to form chemically adsorbed NO₃, which reacts with adsorbed NO and transforms into NO₂ and N₂O₄. A detailed adsorption reaction mechanism of NO with O₂ is shown in Scheme 1.

At the beginning of the NO oxidation reaction, the main behavior is NO adsorption and then reaction with gaseous O₂. The adsorbed NO₃ from the NO oxidation continues to react with adsorbed NO to give NO₂ and N₂O₄, which physically adsorb onto Na-ZSM-5 with a high adsorption volume and NO₂ is not released during this period. This stage corresponds to 0–15 min as shown in Fig. 1. NO oxidation in the first stage is constrained as the reaction progresses and the concentration of NO in the outlet increases slowly because the amount of NO_x adsorption, especially NO₂ adsorption, on Na-ZSM-5 kept increasing. This period is the second stage and corresponds to 15–60 min, as shown in Fig. 1. When NO₂ reaches the saturated adsorption stage and is released, the vacant adsorption sites increase and the reaction of NO₃ with NO increases leading to a sharp decrease in the outlet NO concentration. Finally, the whole process reaches a dynamic equilibrium state between NO₂ desorption and the reaction of NO. This adsorption-reaction mechanism explains the transient profiles in the oxidation reaction pathway of NO with O₂ over Na-ZSM-5, as shown in Fig. 1. It also explains why NO₂ was not be detected in the outlet for NO-O₂-TPSR and NO₂-TPSR and the process for NO₃ adsorption on the surface of Na-ZSM-5 as well as the decomposition into NO and O₂ at high temperature.

3 Conclusions

High silica content Na-ZSM-5 molecular sieves exhibit high catalytic activity at ambient temperature because of the active adsorption sites consisting of -OH groups and Na⁺ ions. During the catalytic oxidation of NO by O₂, Na-ZSM-5 weakly adsorbs NO₂, which mainly physically adsorbs on the surface. The oxidation reaction mechanism of NO with O₂ can be explained as follows: (1) chemical adsorption of NO onto the surface of Na-ZSM-5 and the formation of chemi-

cally adsorbed NO₃ by the reaction of adsorbed NO and gaseous O₂; (2) The formation and sequential physical adsorption of NO₂ and N₂O₄ by the reactions of NO and NO₃; (3) the release of NO₂ and N₂O₄ after saturated adsorption and a subsequent reaction-adsorption dynamic equilibrium. The strong adsorption of NO₃ acts as an intermediate for NO oxidation by O₂ and NO adsorption is also improved.

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